
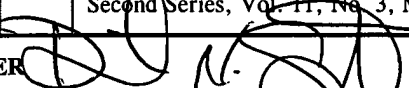


FORM PTO - 1449 INFORMATION DISCLOSURE STATEMENT				ATTORNEY DOCKET NO.: MIT-106 APPLICANT: Michael Mermelstein SERIAL NO.: 09/2746,601 FILING DATE: March 23, 1991					
				RECEIVED JUL 30 1999 TECHNICAL CENTER 2800					
U.S. PATENT DOCUMENTS									
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE		
DNS	A1	Re. 35,930	10/20/98	Brueck et al.	430	311	04/22/96		
DNS	A2	5,771,098	06/23/98	Ghosh et al.	356	363	09/27/96		
DNS	A3	5,759,744	06/02/98	Brueck et al.	430	312	03/16/95		
DNS	A4	5,705,321	01/06/98	Brueck et al.	430	316	06/06/95		
DNS	A5	5,415,835	05/16/95	Brueck et al.	430	396	09/16/92		
DNS	A6	5,384,573	01/24/95	Turpin	342	179	03/17/93		
FOREIGN PATENT DOCUMENTS									
EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG Y/N
DNS	B1	WO 97/48021	12/18/97	PCT	603F	7/20	06/10/97	N	Yes
DNS	B2	GB 2142427A	1/16/85	UK	601B	11/30	5/21/84	N	Yes
OTHER ART, JOURNAL ARTICLES, ETC.									
EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)								
DNS	C1	Anderson, et al. "Holographic lithography with thick photoresist," <i>Appl. Phys. Lett.</i> , Vol. 43, No. 9, November 1, 1983, pp. 874-876.							
DNS	C2	Brueck, S. "Imaging interferometric lithography," <i>Microlithography World</i> , Winter 1998, pp. 2-7.							
DNS	C3	Brueck, et al. "Interferometric lithography - from periodic arrays to arbitrary patterns," <i>Microelectronic Engineering</i> , 41/42 (1998), pp. 145-148.							
DNS	C4	Chen et al. "Interferometric lithography of sub-micrometer sparse hole arrays for field-emission display applications," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 14, No. 5, Sept/Oct 1996, pp. 3338-3349.							
DNS	C5	Chen et al. "Process development for 180-nm structures using interferometric lithography and I-line photoresist," <i>SPIE - The International Society for Optical Engineering</i> , Vol. 3048, March 10-11, 1997, pp. 309-318.							
EXAMINER				DATE CONSIDERED					

FORM PTO - 1449 INFORMATION DISCLOSURE STATEMENT		ATTORNEY DOCKET NO.: MIT-106 APPLICANT: Michael Mermelstein SERIAL NO.: 09/2746,601 FILING DATE: March 23, 1991 GROUP: ²⁸⁷³Not Yet Assigned 3-23-99
DNS	C6	Farhoud et al. "Fabrication of Large Area Nanostructured Magnets by Interferometric Lithography," <i>IEEE Transactions on Magnetics</i> , Vol. 34., No. 4, Pt. 1, July 1998, pp. 1087-1089.
DNS	C7	Ferrera et al. "Analysis of distortion in interferometric lithography," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 14, No. 6, Nov/Dec 1996, pp. 4009-4013.
DNS	C8	Naqvi et al. "Diffractive techniques for lithographic process monitoring and control," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 12, No. 6, Nov/Dec 1994, pp. 3600-3607.
DNS	C9	Savas et al. "Large-area achromatic interferometric lithography for 100 nm period gratings and grids," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 14, No. 6, Nov/Dec 1996, pp. 4167-4170.
DNS	C10	Savas et al. "Achromatic interferometric lithography for 100-nm-period gratings and grids," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 13, No. 6, Nov/Dec 1995, pp. 2732-2735.
DNS	C11	Schattenburg et al. "Fabrication of high energy x-ray transmission gratings for AXAF," <i>SPIE-The International Society for Optical Engineering</i> , Vol 2280, pp. 181-190.
DNS	C12	Schattenburg et al. "Optically matched trilevel resist process for nanostructure fabrication," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 13, No. 6, Nov/Dec 1995, pp. 3007-3011.
DNS	C13	Spallas et al. "Field emitter array mask patterning using laser interference lithography," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 13, No. 6, Sept/Oct 1995, pp. 1973-1978.
DNS	C14	Zaidi et al. "Interferometric lithography exposure tool for 180-nm structures," <i>SPIE-The International Society for Optical Engineering</i> , Vol. 3048, March 10-11, 1997, pp. 248-254.
DNS	C15	Zaidi et al. "Multiple-exposure interferometric lithography," <i>Journal of Vacuum Science & Technology B</i> , Second Series, Vol. 11, No. 3, May/Jun 1993, pp. 658-666.
EXAMINER 		DATE CONSIDERED 6/19/00

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